



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Huey-Chiang Liou et al.	§	Group Art Unit:	2823
		§		
Serial No.:	10/695,103	§		
		§	Examiner:	Trung Q. Dang
Filed:	October 28, 2003	§		
		§		
For:	Langmuir-Blodgett Chemically Amplified Photoresist	§	Atty. Dkt. No.:	ITL.1054US (P17790)
		§		
Customer	21906	§	Confirmation No.:	4735
No.:				

Mail Stop-Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

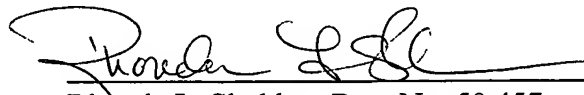
Dear Sir:

Applicant submits the references listed on the attached form PTO 1449 together with any required copies of such references.

This statement is being filed after a first Office action on the merits, but before receipt of a final Office action, a Notice of Allowance or an action that otherwise closes prosecution in the application. A check for \$180 in payment of the late submission fee of §1.17(p) is enclosed. Please apply any additional charges or credits to Deposit Account No. 20-1504(ITL.1054US).

Respectfully submitted,

Date: October 26, 2004

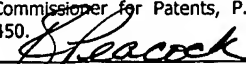

Rhonda L. Sheldon, Reg. No. 50,457
TROP, PRUNER & HU, P.C.
8554 Katy Freeway, Suite 100
Houston, Texas 77024
(713) 468-8880 [Phone]
(713) 468-8883 [Fax]

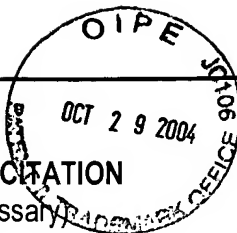
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180.00 DP

Date of Deposit: October 26, 2004
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.


**INFORMATION DISCLOSURE CITATION**

(Use several sheets if necessary)

ATTY DOCKET NO.
ITL 1054US(P17790)SERIAL NO.
10/695,103APPLICANT(S):
Huey-Chiang Liou et al.FILING DATE:
October 28, 2003GROUP ART UNIT:
2823**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AJ							
	AK							
	AL							
	AM							
	AN							
	AO							
	AP							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

AQ	S. Elhadj, J. W. Woody, V. S. Niu and R. F. Saraf, <i>Orientation of self-assembled block copolymer cylinders perpendicular to electric field in mesoscale film</i> , Applied Physics Letters, vol. 82, no. 6, 10 Feb. 2003, p. 871-3.
AR	Huiwen Liu, Bharat Bhushan, <i>Orientation and relocation of biphenyl thiol self-assembled monolayers under sliding</i> , Ultramicroscopy, vol. 91, no. 1-4, May 2002, p. 177-83.
AS	Sang Jung Ahn, Yun Kyeong Jang, Haeseong Lee, and Haiwon Lee, <i>Mechanism of atomic force microscopy anodization lithography on a mixed Langmuir-Blodgett resist of palmitic acid and hexadecylamine on silicon</i> , Applied Physics Letters, vol. 80, no. 14, 8 April 2002, p. 2592-4.
AT	Tiesheng Li, Masaya Mitsuishi, and Tokuji Miyashita, <i>Photodegradable polymer LB films for nano-lithographic imaging techniques</i> , Thin Solid Films, vol. 389, no. 1-2, 15 June 2001, p. 267-71.

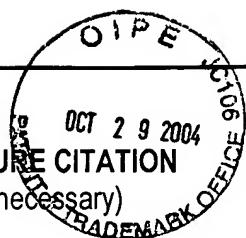
EXAMINE

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APPLICANT(S): Huey-Chiang Liou et al.	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

BA	N.G. Semaltianos, H. Araujo, and E.G. Wilson, <i>Polymerization of Langmuir-Blodgett films of diacetylenes</i> , Surface Science, vol. 460, no. 1-3, 20 July 2000, p. 182-9.
BB	Hiroyuki Sugimura, Atsushi Hozumi and Osamu Takai, <i>Fabrication of Coplanar Microstructures Composed of Multiple Organosilane Self-Assembled Monolayers</i> , IEICE Transactions on Electronics, vol. E83-C, no. 7, July 2000, p. 1099-103.
BC	M. Sundermann, J. Hartwich, K. Rott, D. Meyners, E. Majkova, U. Kleineberg, M. Grunze, U. Heinzmann, <i>Nanopatterning of Au absorber films on Mo/Si EUV multilayer mirrors by STM lithography in self-assembled monolayers</i> , Surface Science, vol. 454-456, 20 May 2000, p. 1104-9.
BD	Richard D. Peters, Xiao M. Yang, Tae K. Kim, B. H. Sohn, and Paul F. Nealey, <i>Using Self-Assembled Monolayers Exposed to X-rays To Control the Wetting Behavior of Thin Films of Diblock Copolymers</i> , Langmuir, vol. 16, no. 10, 16 May 2000, p. 4625-31.
BE	Hiroyuki Sugimura, Kazuya Ushiyama, Atsushi Hozumi, and Osamu Takai, <i>Micropatterning of Alkyl- and Fluoroalkylsilane Self-Assembled Monolayers Using Vacuum Ultraviolet Light</i> , Langmuir, vol. 16, no. 3, 8 Feb. 2000, p. 885-8.
BF	Hiroyuki Maruyama, Nobuyuki Kosai, Tadatake Sato, Shigehito Sagisaka, Hiroshi Segawa, Takeo Shimidzu and Kazuyoshi Tanaka, <i>Nanometer-Scale Lithography on the Oligosilane Langmuir-Blodgett Film</i> , Japanese Journal of Applied Physics, Part 1, vol. 36, no. 12A, Dec. 1997, p. 7312-16.
BG	Chang Nam Kim, Dong Woo Kang, Eung Ryul Kim, and Haiwon Lee, <i>Fabrication of a Polymethylphenylmethacrylate Resist by Using Electron Beam Lithography</i> , Journal of the Korean Physical Society, vol. 31, no. 1, July 1997, p. 154-7.
BH	T. Sato, and H. Ahmed, <i>Observation of a Coulomb staircase in electron transport through a molecularly linked chain of gold colloidal particles</i> , Applied Physics Letters, vol. 70, no. 20, 19 May 1997, p. 2759-61.
BI	Earl T. Ada, Luke Hanley, Sergei Etchin, John Melngailis, Walter J. Dressick, Mu-San Chen and Jeffrey M. Calvert, <i>Ion beam modification and patterning of organosilane self-assembled monolayers</i> , Journal of Vacuum Science & Technology B, vol. 13, no. 6, Nov.-Dec. 1995, p. 2189-96.
BJ	
BK	
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